RF SPUTTERING OF ITO ON ROTARY CATHODES

J. German, R. Lovro

Sputtering Components, Inc., 375 Alexander Drive, Owatonna, Minnesota, USA

Recent developments in sputter deposition of ITO include the application of RF power, which has been demonstrated to significantly improve the electrical and optical properties of the deposited film. Previously, this technique had been applied only to planar targets. Known advantages of rotary targets, compared to planar targets, impel expanding the use of RF to rotary. Results of RF power applied to rotary ITO targets are reported.